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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF: :  
ATSUSHI SHIOTA ET AL. : GROUP ART UNIT: 1712  
SERIAL NO: 09/770,289 : EXAMINER: FEELY, M.  
FILED: JANUARY 29, 2001 : RCE FILED: HERewith

FOR: PROCESS FOR PRODUCING  
SILICA-BASED FILM, SILICA-  
BASED FILM, INSULATING FILM,  
AND SEMICONDUCTOR DEVICE

AMENDMENT

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VA 22313-1450

SIR:

Further to the Request for Continued Examination filed herewith, and in response to the Final Rejection dated June 9, 2003, please amend the application identified above as follows.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/ Arguments** begin on page 7 of this paper